

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	:	Sato et al.
Appl. No.	:	10/540,056
Filed	:	June 22, 2005
For	:	POSITIVE RESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN
Examiner	:	Chu, John S.Y.
Group Art Unit	:	1795

**RESPONSE TO OFFICE ACTION****Mail Stop Amendment**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **April 21, 2008**, please consider the following remarks.

**The listing of claims** begins on page 2 of this paper. No amendments have been made.

**Remarks** begin on page 6 of this paper.